

Atmospheric Substrate Processing Apparatus for Depositing Multiple Layers on a Substrate

ABSTRACT OF THE DISCLOSURE

A substrate processing apparatus is disclosed. In one embodiment, the
5 apparatus includes a first atmospheric deposition station and a second atmospheric deposition
station. The second atmospheric deposition station comprises an atmospheric pressure vapor
deposition chamber. A substrate handling system is adapted to transfer substrates between
the first and the second atmospheric deposition stations.

10 SF 1200876 v1